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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
09/963,465	09/27/2001	Koji Hasegawa	KOJIM-428	9545
23599	7590 10/20/2003		EXAMINER	
	HITE, ZELANO & B	THORNTON, YVETTE C		
2200 CLARE	NDON BLVD.		ART UNIT	PAPER NUMBER
SUITE 1400 ARLINGTO	N, VA 22201		1752	

DATE MAILED: 10/20/2003

Please find below and/or attached an Office communication concerning this application or proceeding.

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•		Application N .	Applicant(s)	
Office Action Summary		09/963,465	HASEGAWA ET AL.	
		Examin r	Art Unit	
		Yvette C. Thornton	1752	
Period f	The MAILING DATE of this communicati r Reply	n appears on the cover sheet w	with the c rrespondenc addre	ess
A SH THE   - External after - If the - If NC - Failu - Any	ORTENED STATUTORY PERIOD FOR R MAILING DATE OF THIS COMMUNICATI nsions of time may be available under the provisions of 37 C SIX (6) MONTHS from the mailing date of this communicatic period for reply specified above is less than thirty (30) days, period for reply is specified above, the maximum statutory pre to reply within the set or extended period for reply will, by eply received by the Office later than three months after the ad patent term adjustment. See 37 CFR 1.704(b).	ON. EFR 1.136(a). In no event, however, may a on. , a reply within the statutory minimum of the period will apply and will expire SIX (6) MC statute, cause the application to become a	a reply be timely filed  irty (30) days will be considered timely.  INTHS from the mailing date of this comma  ABANDONED (35 U.S.C. § 133).	nunication.
1)⊠	Responsive to communication(s) filed or	n <u>04 August 2003</u> .		
2a)⊠	This action is <b>FINAL</b> . 2b)	This action is non-final.		
3) <u> </u>	Since this application is in condition for a closed in accordance with the practice u	allowance except for formal m nder <i>Ex parte Quayl</i> e, 1935 C	atters, prosecution as to the r c.D. 11, 453 O.G. 213.	nerits is
•	on of Claims Claim(s) <u>1-20</u> is/are pending in the applic	cation		
4)🖂	4a) Of the above claim(s) is/are wit			
<b>5</b> \⊠	Claim(s) 1-12 is/are allowed.	and a with the first control and the first c		
	Claim(s) <u>13-20</u> is/are rejected.	•		
•	Claim(s) is/are objected to.			
8)	Claim(s) are subject to restriction a	and/or election requirement.		
,	ion Papers	ana, or oloosion roquilomoniu		
	The specification is objected to by the Exa	aminer.		
10)	The drawing(s) filed on is/are: a)	accepted or b)  objected to by	the Examiner.	
	Applicant may not request that any objection			
11)	The proposed drawing correction filed on	is: a)□ approved b)□	disapproved by the Examiner.	
•	If approved, corrected drawings are required	d in reply to this Office action.		
12)	The oath or declaration is objected to by the	he Examiner.		
Priority :	under 35 U.S.C. §§ 119 and 120			
13)⊠	Acknowledgment is made of a claim for for	oreign priority under 35 U.S.C	. § 119(a)-(d) or (f).	
a)	⊠ All b) Some * c) None of:			
	1. Certified copies of the priority docu	ments have been received.		
	2. Certified copies of the priority docu	ments have been received in	Application No	
* (	<ol> <li>Copies of the certified copies of the application from the Internation See the attached detailed Office action for</li> </ol>	nal Bureau (PCT Rule 17.2(a))	).	age
14) 🔲 ,	Acknowledgment is made of a claim for do	mestic priority under 35 U.S.C	C. § 119(e) (to a provisional a	pplication).
	a)  The translation of the foreign language Acknowledgment is made of a claim for do			
Attachmei				
2) 🔲 Noti	ce of References Cited (PTO-892) ce of Draftsperson's Patent Drawing Review (PTO-94 mation Disclosure Statement(s) (PTO-1449) Paper N	48) 5) Notice	w Summary (PTO-413) Paper No(s). of Informal Patent Application (PTO-	

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#### **DETAILED ACTION**

This is written in reference to application number 09/963,465 filed on September 27, 2001, which was published as US 2002/0061465 A1 on May 23, 2002.

## Response to Amendment

Claims 1-3 and 8 have been amended. Claims 9-20 have been newly added. Claims 1 are currently pending.

## Claim Rejections - 35 USC § 103

- 2. The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:
  - (a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.
- 3. Claims 13-15 and 19-20 are rejected under 35 U.S.C. 103(a) as being unpatentable over Allen et al. (US 5,985,524 A). Allen claims a process for generating a bilayer resist image on a substrate comprising the steps of (a) coating a substrate with an organic underlayer; (b) coating the underlayer with a top layer comprising a radiation sensitive acid generator and a polymer formed by copolymerizing (i) hydroxystyrene with (ii) a second monomer and optionally with (iii) a third monomer optionally substituted with an acid cleavable group; (c) imagewise exposing the top layer to radiation; (d) developing the image in the top layer; and (e) transferring the image through the organic underlayer to the substrate (cl. 29; see also c. 3, l. 49-c. 4, l. 55). The second monomer of the said polymer

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$$H_2C = CR$$

$$\begin{vmatrix}
R_1 \\
COO - (CR'_2)_2 - Si - R_2 \\
R_3
\end{vmatrix}$$

preferably has the structure:

wherein R is hydrogen or

methyl, R' is independently hydrogen,  $C_{1.6}$  alkyl, phenyl or benzyl and  $R_{1.3}$  are independently selected from the group consisting of hydrogen,  $C_{1.6}$  alkyl and  $Si(R_4)_3$  wherein  $R_4$  is independently hydrogen or lower alkyl (cl. 30). It is the examiner's position that the limitations of the instant claims are meet when  $R_{1.3}$  of the taught structure is independently  $C_{1.6}$  alkyl. Specifically, the said monomer would meet the limitations of claimed formula 2 wherein  $R^{1.4}$  is hydrogen or alkyl group having 1-6 carbon atoms, m is 1, and  $R^{5.7}$  are alkyl groups.

Allen also teaches the use of an acrylate or methacrylate polymer having an acid cleavable silylethoxy group attached to the carbonyl group of the (meth)acrylate. The said (meth)acrylate can be copolymerized with comonomers including (i) (meth)acrylate monomers with lower alkyl groups, (ii) (meth)acrylic acid monomers, (iii) (meth)acrylate monomers with other types of acid labile esters groups such as tertiary alkyl ester or (iv) hydroxystyrene (c. 2, l. 53-64). It is the examiner's position that (meth)acrylic acid monomers meet the limitations of claimed formula (73) of instant claims 13 and 14. It would have been obvious to one of ordinary skill in the art to substitute the hydroxystyrene of claim 30/29 for a/an (meth)acrylic acid monomer and expect reasonably similar results.

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4. Claims 16-18 are rejected under 35 U.S.C. 103(a) as being unpatentable over Allen et al. (US 5,985,524 A) as applied to claims 13-15 and 19-20 above, and further in view of Allen et al. (US 5,580,694 A) and Choi (US 6,045,970 A).

Allen ('524) teaches all the limitations of the instant claims except it fails to claim the use of a basic compound and a dissolution inhibitor as set forth in instant claims 16-18.

Allen does however teach that the top imaging layer may optionally comprise other minor components such as dissolution inhibitors, coating enhancers, surfactants, bases and other compounds know to those in the art (c. 3, l. 38-41).

Allen (US 5,580,694) teaches the use of a mono-, di- or tri-protected hydroxy androstane-17-alkylcarboxylate as conventional dissolution inhibitors. Photogenerated free acid causes cleavage of the alkylcarboxylate ester to form free acid, converting the androstane molecule from dissolution inhibitor to dissolution enhancer. Preferred compounds are t-butyl 3-acetyllithocholate and t-butyl 3-trifluoroacetyllithocholate (c. 3, l. 1-46). One of ordinary skill in the art would have been motivated by the teaching of Allen to incorporate a dissolution inhibitor having an acid labile group such as t-butyl 3-acetyllithocholate and t-butyl 3-trifluoroacetyllithocholate into the taught composition of Allen ('254) in order to improve the etch resistance for subsequent process steps (Allen '694 c. 4, l. 54-55).

Choi (US 6,045,970 A) teaches that organic bases such as triethylamine, triisobutylamine and triethanolamine are used in photoresist compositions to prevent a decrease in the critical size of the pattern after exposure, caused by acid diffusing from an exposed portion of the photoresist to an unexposed portion (c. 4, l. 23-31). One of ordinary skill in the art would have been motivated by the teaching of Choi to incorporate a base such

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as triethylamine, triisobutylamine and triethanolamine into the taught composition of Allen ('524) in order to decrease the critical size of the pattern after exposure (Choi c. 4, l. 23-31).

## Response to Arguments

- 5. Applicant's arguments, with respect to instant claims 1-12 have been fully considered and are persuasive. The rejections of the said claims over prior art references of Allen and Brock have been withdrawn.
- 6. Applicants have submitted new claims 13-20, which contain a definition for R1 and R2, which was presented in the original claims. The examiner is of the position that the prior art reference of Allen, as discussed above, it still applicable to claims 13-20 as presented.

## Allowable Subject Matter

- 7. Claims 1-12 are allowed.
- 8. The following is an examiner's statement of reasons for allowance: by Allen et al. (US 5,985,524 A). Allen claims a polymer comprising the structure:

$$H_2C = CR$$
 $|$ 
 $COO - (CR'_2)_2 - Si - R_2$ 
 $|$ 
 $R_3$ 

wherein R is hydrogen or methyl, R' is independently hydrogen,  $C_{1-6}$  alkyl, phenyl or benzyl and  $R_{1-3}$  are independently selected from the group consisting of hydrogen,  $C_{1-6}$  alkyl and  $Si(R_4)_3$  wherein  $R_4$  is independently hydrogen or lower alkyl (cl. 30). The prior art reference of Allen fails to teach and/or suggest a compound wherein at least one of R1 and R2 is a  $C_1$ . Cyclic alkyl group and the other is hydrogen.

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9. Any comments considered necessary by applicant must be submitted no later than the payment of the issue fee and, to avoid processing delays, should preferably accompany the issue fee. Such submissions should be clearly labeled "Comments on Statement of Reasons for Allowance."

#### Conclusion

- 10. Applicant's amendment necessitated the new ground(s) of rejection presented in this Office action. Accordingly, **THIS ACTION IS MADE FINAL**. See MPEP § 706.07(a). Applicant is reminded of the extension of time policy as set forth in 37 CFR 1.136(a).
- 11. A shortened statutory period for reply to this final action is set to expire THREE MONTHS from the mailing date of this action. In the event a first reply is filed within TWO MONTHS of the mailing date of this final action and the advisory action is not mailed until after the end of the THREE-MONTH shortened statutory period, then the shortened statutory period will expire on the date the advisory action is mailed, and any extension fee pursuant to 37 CFR 1.136(a) will be calculated from the mailing date of the advisory action. In no event, however, will the statutory period for reply expire later than SIX MONTHS from the date of this final action.
- 12. Any inquiry concerning this communication or earlier communications from the examiner should be directed to Yvette C. Thornton whose telephone number is 703-305-0589. The examiner can normally be reached on Monday-Thursday 8-6:30.
- 13. If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Janet C. Baxter can be reached on 703-308-2303. The fax phone number for the organization where this application or proceeding is assigned is (703) 872-9306.

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14. Any inquiry of a general nature or relating to the status of this application or proceeding should be directed to the receptionist whose telephone number is 703-308-1495.

yct (/) October 9, 2003

JANET BAXTER
SUPERVISORY PATENT EXAMINER
TECHNOLOGY CENTER 1700